

10/648,243 : c A Reg. File struc.
search cl. 1, form 1-3, 6,
als w/ Nb-lactone, 6/25/06, R9A

(FILE 'HOME' ENTERED AT 17:47:14 ON 25 JUN 2006)

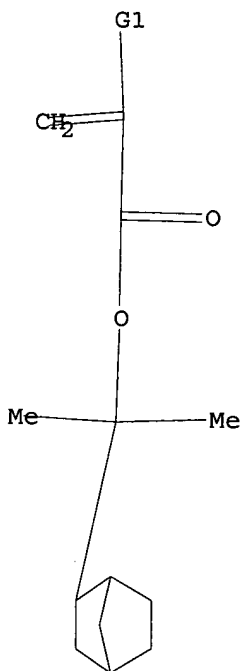
FILE 'REGISTRY' ENTERED AT 17:47:38 ON 25 JUN 2006

L1 SCREEN 963 AND 970 AND 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 SCREEN 970 AND 2067
L5 STRUCTURE UPLOADED
L6 QUE L5 AND L4
L7 SCREEN 970 AND 2067
L8 STRUCTURE UPLOADED
L9 QUE L8 AND L7
L10 SCREEN 970 AND 2067
L11 STRUCTURE UPLOADED
L12 QUE L11 AND L10

=> d 13

L3 HAS NO ANSWERS

L1 SCR 963 AND 970 AND 2067
L2 STR



Form (6)

G1 H, Me

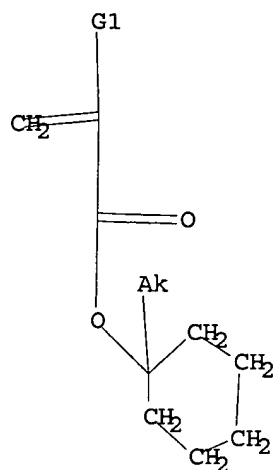
Structure attributes must be viewed using STN Express query preparation.

L3 QUE L2 AND L1

=> d 16

L6 HAS NO ANSWERS

L4 SCR 970 AND 2067
L5 STR



form(3)

G1 H, Me

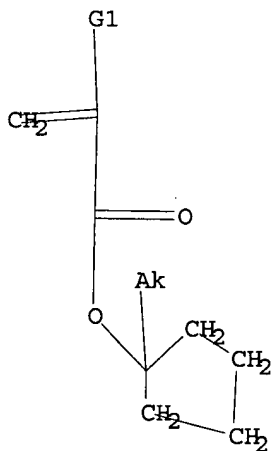
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=> d 19

L9 HAS NO ANSWERS

L7 SCR 970 AND 2067

L8 STR



form(2)

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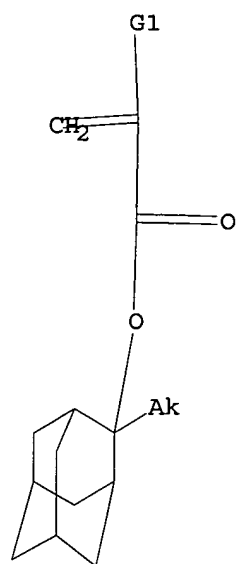
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L9 QUE L8 AND L7

=> d 112

L12 HAS NO ANSWERS

L10 SCR 970 AND 2067

L11 STR



FORM (1)

G1 H, Me

Structure attributes must be viewed using STN Express query preparation.
L12 QUE L11 AND L10

=> d his

(FILE 'HOME' ENTERED AT 17:47:14 ON 25 JUN 2006)

FILE 'REGISTRY' ENTERED AT 17:47:38 ON 25 JUN 2006

L1	SCREEN 963 AND 970 AND 2067
L2	STRUCTURE UPLOADED
L3	QUE L2 AND L1
L4	SCREEN 970 AND 2067
L5	STRUCTURE UPLOADED
L6	QUE L5 AND L4
L7	SCREEN 970 AND 2067
L8	STRUCTURE UPLOADED
L9	QUE L8 AND L7
L10	SCREEN 970 AND 2067
L11	STRUCTURE UPLOADED
L12	QUE L11 AND L10

=>

FILE 'REGISTRY' ENTERED AT 17:47:38 ON 25 JUN 2006

L1 SCREEN 963 AND 970 AND 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 SCREEN 970 AND 2067
L5 STRUCTURE UPLOADED
L6 QUE L5 AND L4
L7 SCREEN 970 AND 2067
L8 STRUCTURE UPLOADED
L9 QUE L8 AND L7
L10 SCREEN 970 AND 2067
L11 STRUCTURE UPLOADED
L12 QUE L11 AND L10
L13 58 S L3 FULL Form 6
L14 165 S L6 FULL Form 3
L15 283 S L9 FULL Form 2
L16 1882 S L12 FULL Form 1
L17 1 S L13 AND (L14 OR 15 OR 16)

FILE 'CAPLUS' ENTERED AT 17:54:20 ON 25 JUN 2006

L18 1 S L17

FILE 'REGISTRY' ENTERED AT 17:55:22 ON 25 JUN 2006

=> s l14 and (l15 or l14 or l16)
L19 165 L14 AND (L15 OR L14 OR L16)

=> d 1-40 bib hitstr
'BIB' IS NOT A VALID FORMAT FOR FILE 'REGISTRY'
'HITSTR' IS NOT A VALID FORMAT FOR FILE 'REGISTRY'

The following are valid formats:

Substanc

3 58 S L3 FULL
L14 165 S L6 FULL
L15 283 S L9 FULL
L16 1882 S L12 FULL
L17 1 S L13 AND (L14 OR 15 OR 16)

FILE 'CAPLUS' ENTERED AT 17:54:20 ON 25 JUN 2006

=> s l17

L18 1 L17

=> d bib

L18 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2006 ACS on STN
AN 2003:855512 CAPLUS
DN 139:343483
TI Radiation-sensitive resin composition
IN Nishimura, Yukio; Ishii, Hiroyuki; Yamamoto, Masafumi; Nishimura, Isao
PA Japan
SO U.S. Pat. Appl. Publ., 26 pp.
CODEN: USXXCO
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	-----	----	-----	-----	-----
PI	US 2003203309	A1	20031030	US 2003-386707	20030313
	JP 2003337419	A2	20031128	JP 2003-66164	20030312
PRAI	JP 2002-71696	A	20020315		

L20 ANSWER 29 OF 32 CAPLUS COPYRIGHT 2006 ACS on STN
 AN 2003:855512 CAPLUS
 DN 139:343483
 TI Radiation-sensitive resin composition
 IN Nishimura, Yukio; Ishii, Hiroyuki; Yamamoto, Masafumi; Nishimura, Isao
 PA Japan
 SO U.S. Pat. Appl. Publ., 26 pp.
 CODEN: USXXCO
 DT Patent
 LA English
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2003203309	A1	20031030	US 2003-386707	20030313
	JP 2003337419	A2	20031128	JP 2003-66164	20030312
PRAI	JP 2002-71696	A	20020315		

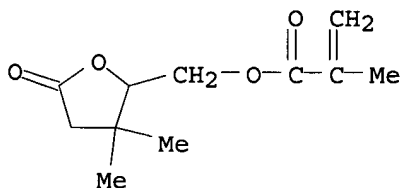
AB A radiation-sensitive resin composition suitable as a chemical amplified resist useful for microfabrication comprises: (A) a resin insol. or scarcely soluble in alkali, but becomes alkali soluble by the action of an acid and (B) a photoacid generator. The resin comprises at least one recurring unit of the following formula I (R1 = H, methyl; A1 = single bond, X1-COO-; X1 = methylene, alkylene with less with 10 carbon atoms; R2 = C1-6 alkyl; n = 0, 1; R3 = H, C1-6 alkyl, oxygen containing group), II (R4 = H, methyl; A2 = single bond, X2-COO-; X2 = methylene, alkylene with less with 10 carbon atoms; R5 = C1-4 alkyl, C4-20 monovalent alicycli hydrocarbon group).

IT 617711-90-7P 617711-95-2P
 RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (radiation-sensitive resin composition for microfabrication containing)

RN 617711-90-7 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 1-ethylcyclopentyl ester, polymer with hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl 2-methyl-2-propenoate, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and (tetrahydro-3,3-dimethyl-5-oxo-2-furanyl)methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

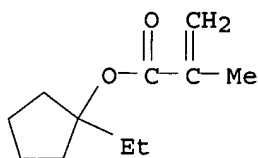
CRN 379257-69-9
 CMF C11 H16 O4



Handwritten notes:
 10/28/04
 Used in 1/27/08

CM 2

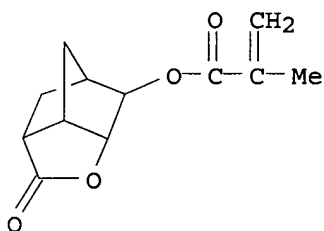
CRN 266308-58-1
 CMF C11 H18 O2



CM 3

CRN 254900-07-7

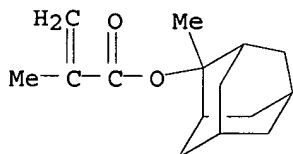
CMF C12 H14 O4



CM 4

CRN 177080-67-0

CMF C15 H22 O2



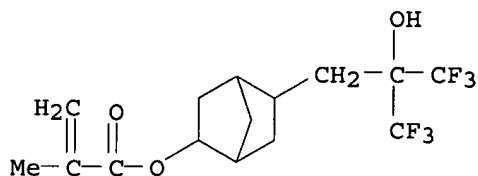
RN 617711-95-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl ester, polymer with 1-methylcyclopentyl 2-methyl-2-propenoate, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and 5-[3,3,3-trifluoro-2-hydroxy-2-(trifluoromethyl)propyl]bicyclo[2.2.1]hept-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

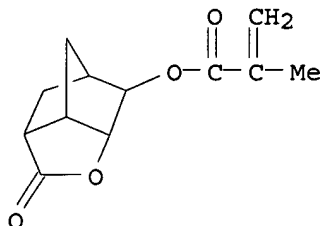
CRN 617711-94-1

CMF C15 H18 F6 O3



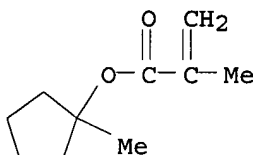
CM 2

CRN 254900-07-7
CMF C12 H14 O4



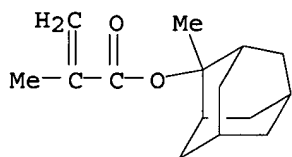
CM 3

CRN 178889-45-7
CMF C10 H16 O2



CM 4

CRN 177080-67-0
CMF C15 H22 O2



L20 ANSWER 31 OF 32 CAPLUS COPYRIGHT 2006 ACS on STN
AN 2002:84088 CAPLUS
DN 136:119239
TI New copolymers for deep UV workable photoresists with good light transmittance and high sensitivity and resolution and method for forming resist patterns with high aspect ratio using the copolymers
IN Nakamura, Takeshi; Ikegawa, Taeko; Sawano, Atsushi; Doi, Kosuke; Ohara, Hidekatsu
PA Tokyo Ohka Kogyo Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 14 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002030116	A2	20020131	JP 2000-214450	20000714
	TW 556046	B	20031001	TW 2001-90116169	20010702

US 2002031719	A1	20020314	US 2001-901646	20010711
US 6517993	B2	20030211		
DE 10134162	A1	20020425	DE 2001-10134162	20010713
DE 10134162	B4	20051020		
PRAI JP 2000-214450	A	20000714		

AB The copolymers bear units derived from (meth)acrylic acid 1-(C1-4 alkyl)cyclohexyl esters, unsatd. acid anhydrides, and optionally allyltrimethylsilane or/and 2-(C1-4 alkyl)-2-adamantyl (meth)acrylate, and are used in a photoresist composition containing photochem. acid formers and organic

solvents. Thus, mixing 1-ethyl-1-cyclohexyl methacrylate 7.4 with 2-methyl-2-adamantyl methacrylate 5.3, maleic anhydride 0.9, allyltrimethylsilane 7.3 and AIBN 0.6 in EtOAc 69.4 parts at room temperature for 60 min, heating at 70° for 22 h and working up gave a copolymer with Mw 18,400 and polydispersity 1.54, which was dissolved in propylene glycol monomethyl ether acetate to 7% concentration, mixed at 30 g with 4-(MeO)C6H4(Ph)2S+C4F9SO3- 0.258 g, and filtered to give a photoresist with photo-sensitivity 60 J/cm2, resolution 0.17 µm and focusing deep width 0.5 µm.

IT 391208-99-4P, Allyltrimethylsilane;1-ethyl-1-cyclohexyl methacrylate;maleic anhydride;2-methyl-2-adamantyl methacrylate copolymer
 RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (new copolymers for deep UV workable photoresists with good light transmittance and high sensitivity and resolution and method for forming resist patterns with high aspect ratio using copolymers)

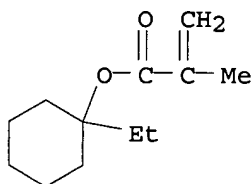
RN 391208-99-4 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 1-ethylcyclohexyl 2-methyl-2-propenoate, 2,5-furandione and trimethyl-2-propenylsilane (9CI) (CA INDEX NAME)

CM 1

CRN 274248-09-8

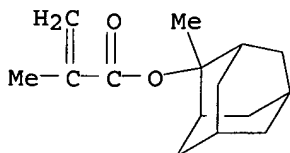
CMF C12 H20 O2



CM 2

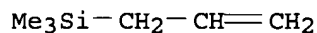
CRN 177080-67-0

CMF C15 H22 O2



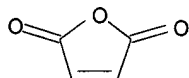
CM 3

CRN 762-72-1
CMF C6 H14 Si



CM 4

CRN 108-31-6
CMF C4 H2 O3



L20 ANSWER 32 OF 32 CAPLUS COPYRIGHT 2006 ACS on STN
AN 2000:624801 CAPLUS
DN 133:215460
TI Positive-working far UV-sensitive resist composition
IN Kodama, Kunihiro; Sato, Kenichiro; Aogo, Toshiaki
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 36 pp.
CODEN: JKXXAF

DT Patent
LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000241977	A2	20000908	JP 1999-44978	19990223
PRAI	JP 1999-44978		19990223		

AB The pos.-working far UV-sensitive resist composition has a photoacid generator and a resin, which has -O-C(R')(R'')(X-COR) (R', R'' = alkyl, cyclic hydrocarbon; X = single bond, divalent connecting group; R = alkoxy, amide, amino, etc.) group in the side chain, increasing the solubility towards an alkali developer upon reacting with an acid. The composition having the resin is suitable for exposure with ≤ 250 nm far UV light.

IT 290304-61-9P

RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

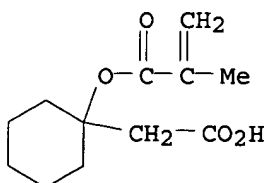
(resin in pos.-working far UV sensitive resist composition)

RN 290304-61-9 CAPLUS

CN Cyclohexaneacetic acid, 1-[(2-methyl-1-oxo-2-propenyl)oxy]-, polymer with 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

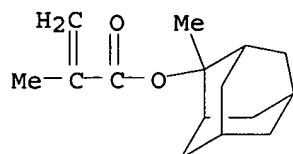
CRN 290304-60-8
CMF C12 H18 O4



CM 2

CRN 177080-67-0

CMF C15 H22 O2



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EAST - [648243all.wsp:1]

File View Edit Tools Window Help

S29: (85) (cyclopentane or cyclopentyl) near2 (methacrylate or acrylate)
S30: (1770) (cyclohexane or cyclohexyl) near2 (methacrylate or acrylate)
S31: (60) (norbornane or norbornyl) near2 (methacrylate or acrylate)
S32: (147) (adamantane or adamantyl) with (cyclopentane or cyclopentyl)
S33: (405) (adamantane or adamantyl) with (cyclohexane or cyclohexyl)
S34: (3823) photoacid or sulfonium
S35: (14211) (adamantyl or cyclopentane or cyclopentyl or cyclohexane or cyclohexyl)
S36: (433) (adamantane or adamantyl) with (cyclohexane or cyclohexyl or cyclopentane)
S37: (8069) (adamantane or adamantyl) with (cyclohexane or cyclohexyl or cyclopentane)
S38: (769) S35 and S37
S39: (22109) photoacid or sulfonium
S40: (439) S38 and S39
S41: (19619) sulfonium
S42: (403) S38 and S41
S44: (33) norbornane adj lactone
S43: (5) norbornyl adj lactone
S45: (1252) (adamantyl or adamantane) near2 (methacrylate or acrylate)
S46: (653) (cyclopentane or cyclopentyl) near2 (methacrylate or acrylate)
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S48: (614) (norbornane or norbornyl) near2 (methacrylate or acrylate)
S49: (403) S42 and (S45 or S46 or S47 or S48)
S50: (176430) photoresist or resist adj composition
S51: (342) S49 and S50

Search List Browse Queue Clear
DBs US-PGPUB: USPAT: USOCR: EPO: J Plurals
Default operator: OR Highlight all hit terms initially
(norbornane or norbornyl) near2 (methacrylate or acrylate)

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U	1	Document ID	Issue Date	Pages	Title	Current OR	Current XRef	Re
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Hits Details HTML

Ready CAP NUM

C = Text search, uspat, uspgpub, epo, sp, derwent, IBM-td
6/25/07, R9A